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EXPEDITED PROCEDURE
BOX ISSUE FEE
Examining Group 1752

ASA-481-05

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re Patent Application of

N. HASEGAWA et al

BATCH NO: R95

Official
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Serial No. 09/188,368

Group Art Unit: 1752

Filed: November 10, 1998

Examiner: S. Rosasco

For: PHOTOMASK AND PATTERN FORMING METHOD EMPLOYING THE SAME

AMENDMENT UNDER 37 C.F.R. §1.312(a)

(OK to
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BOX ISSUE FEE

Assistant Commissioner of Patents
Washington, D.C. 20231

July 7, 1999

Sir:

Further to the Supplemental Notice of Allowability,
mailed May 13, 1999, please further amend the above
application as set forth below.

IN THE CLAIMS

Please amend claims 18 and 43 as set forth below.

9.
18. (Amended) A pattern forming method comprising the
steps of:

mounting a substrate having a to-be-exposed film, on a
sample stage of an aligner having a masking blade;

mounting, on a mask support of said aligner, a
semitransparent phase shifting mask including (a) a first
semitransparent phase shifting pattern having a

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